

ABSTRACT

A cleaning method is provided for an ultrapure water supply system having an ultrapure water production apparatus connected to a point of use of ultrapure water via a passage. In the cleaning method, a basic solution, for example, is circulated through the system to change the surface potential of fine particles in the system from an opposite to the same polarity as that of elements constituting the system, thereby facilitating the removal of the fine particles, and the fine particles are then discharged from the system to outside together with the basic solution. The cleaning method has excellent cleaning capability and also makes it possible to shorten the rinsing time required for removing the residual constituent of the cleaning solution.